C1 cont'd

a movable member arranged to relatively move said mask with respect to said rectangular area on said predetermined plane during scanning exposure on a substrate with said illumination beam through said mask, and to hold said mask at a position on or near said predetermined plane.

54. (Amended) A scanning exposure apparatus comprising:

C2

an illumination optical system arranged to illuminate a slit area on a predetermined plane on which a mask is arranged, with an illumination beam, an optical axis of said illumination optical system being substantially perpendicular to said slit area, and said illumination optical system comprising a fly-eye type integrator having a plurality of optical elements each of which has a cross sectional shape that is substantially equal to said slit area on said predetermined plane; and

a movable member arranged to relatively move said mask with respect to said slit area on said predetermined plane during scanning exposure on a substrate with said illumination beam through said mask, and to hold said mask at a position on or near said predetermined plane.

64. (Amended) A scanning exposure apparatus comprising:

C3

an illumination optical system arranged to illuminate a slit area on a predetermined plane on which a mask is arranged, with an illumination beam, an optical axis of said illumination optical system being substantially perpendicular to said slit area on said predetermined plane, and said illumination optical system comprising an optical integrator arranged on said optical axis, which forms a plurality of light source images in which the number of light source images arranged in a first direction corresponding to a longitudinal direction of said slit area is different from a number of light source images arranged in a second direction crossing said first direction; and

C3

a movable member arranged to relatively move said mask with respect to said slit area on said predetermined plane during scanning of said illumination beam on a substrate through said mask, and to hold said mask at a position on or near said predetermined plane.

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76. (Amended) A scanning exposure method comprising the steps of:

C4

illuminating a rectangular area on a predetermined plane on which a mask is arranged with an illumination beam emerging from an internal reflection type integrator, an exit plane of said internal reflection type integrator having a shape substantially equal to a shape of said rectangular area on said predetermined plane; and

relatively moving said mask and a substrate with respect to said illumination beam, respectively, to perform scanning exposure of said substrate with said illumination beam through said mask.

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77. (Twice Amended) A device manufacturing method comprising a step of transferring a device pattern onto a work piece, wherein said transferring step comprises:

C5

illuminating a rectangular area on a predetermined plane on which a mask is arranged with an illumination beam emerging from an internal reflection type integrator, an exit plane of said internal reflection type integrator having a shape substantially equal to a shape of said rectangular area on said predetermined plane; and

relatively moving said mask and said work piece with respect to said illumination beam, respectively, to perform scanning exposure of said work piece with said illumination beam through said mask.

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78. (Amended) A scanning exposure method comprising the steps of:

C6

illuminating a slit area on a predetermined plane on which a mask is arranged with an illumination beam emerging from a fly-eye type integrator having a plurality of optical elements each of which has a cross sectional shape substantially equal to a shape of said slit area on said predetermined plane; and